Cyrus E. Tabery

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Objective:

Attain summer 2000 internship in photolithography, alternative microfabrication processes, or advanced photomask patterning

Education:

The University of Texas at Austin
Bachelor of Science, Chemical engineering, December 2000
Overall GPA: 3.84/ 4.00 Major GPA: 4.00/ 4.00

Related Courses:

Hands on with PROLITH (C. A. Mack), Computer Applications in Chemical Engineering, Engineering Modeling Conference Course, Introduction to Polymer Engineering, Solid State Electronics, Technical Communications, Two Transport Phenomena courses

Experience:

Dr. C. Grant Willson Research Group — April 1998-Present
Department of Chemical Engineering
Undergraduate Thesis: Photoresist Characterization and Lithography Simulation for Photomask Fabrication; Undergraduate research continues in semiconductor fabrication; lithography simulation, photoresist development, optical pattern generator simulation, λ=257 nm resist development for optical pattern generators

IBM Microelectronics, Burlington VT — May 1999-August 1999
Reticle imaging development, process improvement and implementation. Designed bake, exposure, and processing for new resist system. Created qualification plan for implementing new alternating phase shifting reticle imaging process.

Skills:

Mathematical modeling of engineering problems
Photolithography simulation, materials, and processes
Reticle enhancement technique implementation: OPC, PSM
Matlab, Excel, Word, PowerPoint, PROLITH 6 Lithography simulation software

Accomplishments:

SPIE's 1st BACUS Scholarship Recipient	Fall 1999
Best Poster Award at BACUS	Fall 1999
Celanese Undergraduate Research Presentation Winner	1998-1999
OXE Chemical Engineering Honor Society	Fall 1998
EXCEL Undergraduate Research Experience	Summer 1998
NSF Math Modeling Program	Summer 1996
NSF Young Scholars Program for Future Engineers	Summer 1992

Publications:

B. M. Rathsack, C. E. Tabery, P. Tatersall, T. Stachowiak, T. Dallas, M. Pochkowski and C. Grant Willson, *Characterization and Development of a DUV Non-Chemically Amplified Resist for Photomask Fabrication using a 257 nm Optical Pattern Generator* **Bacus (1999).**
B. M. Rathsack, C. E. Tabery, M. Pochkowski, C. Philbin and C. Grant Willson, *Organic Antireflection Coatings for Photomask Fabrication using Optical Pattern Generators* **Bacus (1999)**.
B. M. Rathsack, C. E. Tabery, S. A. Scheer, C. Grant Willson, C. L. Henderson, M. Pochkowski, Cece Philbin, P. D. Buck, *Optical Lithography Simulation and Photoresist Optimization for Photomask Fabrication*, **Proc. SPIE (1999)**.
B. M. Rathsack, C. E. Tabery, S. A. Scheer, C. L. Henderson and C. Grant Willson, *Photoresist Optimization for Laser Photomask Applications*, **Techcon (1998)**.

Reference:

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